

Amendments to the Specification:

Please replace the title as follows:

~~EXPOSURE EQUIPMENT AND METHOD, POSITION CONTROL METHOD AND
DEVICE MANUFACTURING METHOD~~
EXPOSURE APPARATUS, EXPOSURE METHOD, POSITION CONTROL METHOD,
AND METHOD FOR PRODUCING DEVICE

Please replace the paragraph beginning on page 5, line 2, with the following rewritten paragraph:

In order to achieve the object as described above, the present invention adopts the following constructions corresponding to Figs. 1 to 14 as illustrated in embodiments. ~~However, parenthesized symbols affixed to respective elements merely exemplify the elements by way of example, with which it is not intended to limit the respective elements.~~

Please replace the paragraph beginning on page 5, line 9, with the following rewritten paragraph:

According to a first aspect of the present invention, there is provided an exposure apparatus ~~(EX)~~ which exposes a substrate ~~(P)~~ by radiating an exposure light beam ~~(EL)~~ onto the substrate ~~(P)~~ through a liquid ~~(LQ)~~; the exposure apparatus comprising a mover ~~(PST)~~ which is capable of holding the substrate ~~(P)~~; an interferometer system ~~(43)~~ which radiates a measuring light beam ~~(BX, BY, BX01, BX02, BY01, BY02)~~ onto a reflecting surface ~~(MX, MY)~~ formed on the mover ~~(PST)~~ and which receives a reflected light beam therefrom to measure position information about a position of the mover ~~(PST)~~; and a memory ~~(MR)~~ which stores, as first information, error information about an error of the reflecting surface ~~(MX, MY)~~ obtained in the presence of the liquid ~~(LQ)~~ supplied onto the mover ~~(PST)~~.

Please replace the paragraph beginning on page 7, line 2, with the following rewritten paragraph:

According to a second aspect of the present invention, there is provided an exposure apparatus-~~(EX)~~ which exposes a substrate-~~(P)~~ by radiating an exposure light beam-~~(EL)~~ onto the substrate ~~(P)~~ through a liquid ~~(LQ)~~; the exposure apparatus comprising a mover ~~(PST)~~ which holds the substrate; a driving unit-~~(PSTD)~~ which moves the mover-~~(PST)~~; and a control unit ~~(CONT)~~ which controls the driving unit ~~(PSTD)~~ and includes first control information to move the mover ~~(PST)~~ in the presence of the liquid ~~(LQ)~~ supplied onto the mover ~~(PST)~~, and second control information to move the mover ~~(PST)~~ in the absence of the liquid-~~(LQ)~~ supplied onto the mover-~~(PST)~~.

Please replace the paragraph beginning on page 7, line 20, with the following rewritten paragraph:

According to a third aspect of the present invention, there is provided a position control method for controlling a position of a mover ~~(PST)~~ by using a reflecting surface-~~(MX, MY)~~ formed on the mover ~~(PST)~~ which holds a substrate-~~(P)~~ in an exposure apparatus ~~(EX)~~ for exposing the substrate ~~(P)~~ by radiating an exposure light beam ~~(EL)~~ onto the substrate ~~(P)~~ through a liquid ~~(LQ)~~; the position control method comprising measuring error information about an error of the reflecting surface-~~(MX, MY)~~ in the presence of the liquid-~~(LQ)~~ supplied onto the mover-~~(PST)~~; and controlling the position of the mover-~~(PST)~~ on the basis of the error information.

Please replace the paragraph beginning on page 8, line 23, with the following rewritten paragraph:

BEST AVAILABLE COPY

According to a fourth aspect of the present invention, there is provided an exposure apparatus (~~EX2~~) which exposes a substrate by radiating an exposure light beam (~~EL~~) onto the substrate (~~P~~) through a liquid (~~LQ~~); the exposure apparatus (~~EX2~~) comprising an exposure station (~~ST2~~) in which the exposure light beam (~~EL~~) is radiated onto the substrate through the liquid; a measuring station (~~ST1~~) which is provided with a measuring system and in which the substrate is measured and exchanged; a mover (~~PST1, PST2~~) which is movable between the exposure station and the measuring station while holding the substrate; a driving unit (~~PSTD~~) which moves the mover; and a control unit (~~CONT~~) which controls the driving unit and includes first control information for moving the mover in the presence of the liquid supplied onto the mover, and second control information for moving the mover in the absence of the liquid supplied onto the mover; and wherein an exposure is performed for the substrate through the liquid while controlling movement of the mover on the basis of the first control information when the mover (~~PST1, PST2~~) is disposed in the exposure station (~~ST2~~), and measurement is performed while controlling the movement of the mover on the basis of the second control information when the mover is disposed in the measuring station (~~ST1~~).

According to the present invention, the movement of the mover is controlled on the basis of the first control information and the second control information in the exposure station for performing the liquid immersion exposure and the measuring station for performing the measurement respectively. Therefore, the position of the mover can be controlled more correctly in response to the presence or absence of the liquid. It is possible to improve the measurement accuracy and the exposure accuracy.

Please replace the paragraph beginning on page 9, line 26, with the following rewritten paragraph:

According to a fifth aspect of the present invention, there is provided an exposure

apparatus-~~(EX)~~ which exposes a substrate by radiating an exposure light beam onto the substrate through a liquid (~~LQ~~); the exposure apparatus comprising an optical member-~~(2)~~ through which the exposure light beam passes; a mover-~~(PST)~~ which is movable on a light-outgoing side of the optical member (~~2~~); an interferometer system-~~(43)~~ which radiates a measuring light beam onto a reflecting surface-~~(MX, MY)~~ formed on the mover-~~(PST)~~ and which receives a reflected light beam therefrom to measure position information about a position of the mover-~~(PST)~~; and a memory-~~(MRY)~~ which stores, as first information, error information about an error of the reflecting surface-~~(MX, MY)~~ obtained in the presence of a liquid immersion area-~~(AR2)~~ formed on the mover-~~(PST)~~.

Please replace the paragraph beginning on page 10, line 25, with the following rewritten paragraph:

According to a sixth aspect of the present invention, there is provided an exposure method for exposing a substrate by projecting an image of a pattern onto the substrate (~~P~~) through a liquid-~~(LQ)~~; the exposure method comprising holding the substrate-~~(P)~~ or a dummy substrate on a mover-~~(PST)~~ provided with a reflecting surface-~~(MX, MY)~~ onto which a measuring light beam-~~(BX, BY, BX01, BX02, BY01, BY02)~~ for positional measurement; determining error information about an error of the reflecting surface in the presence of the liquid-~~(LQ)~~ supplied onto the mover-~~(PST)~~; and projecting the pattern image onto a predetermined position on the substrate through the liquid on the basis of the error information. According to the exposure method of the present invention, even when the liquid immersion exposure is performed in the state in which the liquid immersion area is formed on the mover, it is possible to correctly perform the relative positional adjustment between the pattern image and the substrate. Therefore, it is possible to maintain the high exposure accuracy brought about by the liquid immersion exposure.